

## **AMENDMENT TO THE ABSTRACT**

The following abstract will replace all prior versions of the abstract in the application:

### **ABSTRACT**

A device for treating a web material in a continuous plasma enhanced process ~~comprises~~ includes a vacuum chamber (1) with device means-(2) for maintaining a constant reduced pressure within the chamber (1) and, arranged within the chamber (1), a rotating drum (3) for supporting and transporting the web (4), a magnetron ~~means~~ device facing the web (4) supported and transported by the drum (3) and a gas supply ~~means~~ device for supplying a process gas or process gas mixture to the space (10) between the drum and the magnetron ~~means~~ device in which space (10) the plasma is sustained. The magnetron ~~means~~ device has ~~comprises~~ a plurality of independent magnetron electrodes (6) with rectangular magnetron faces arranged beside each other in parallel. Each magnetron electrode (6) is individually powered with an alternating voltage by its own power supply ~~means~~ (7). The drum (3) is electrically grounded, floating or negatively biased. ~~The device is in particular applicable for coating a flexible web (4) in a plasma enhanced chemical vapour deposition process, e.g. for coating a web of a polymer film with silicon oxide for improving its barrier properties. The device produces with a high reliability coatings of a very constant quality and needs only little maintenance which can be carried out in a simple manner.~~

(Figure 1)